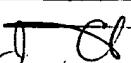
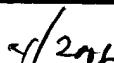


<p style="text-align: center;">O I P A INFORMATION DISCLOSURE CITATION <i>(Use several sheets if necessary)</i></p> <p style="text-align: center;">JUN 3 0 2005</p> <p style="text-align: center;">S C 2005</p>				Docket Number (Optional) 2003US301CIP		Application Number 10/658,840		
				Applicant(s) Ralph R. DAMMEL et al.				
				Filing Date September 9, 2003		Group Art Unit 1752		
U.S. PATENT DOCUMENTS								
*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
FOREIGN PATENT DOCUMENTS								
	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO
JRC		JP 2000 098614 A	4/7/2000	JAPAN				
OTHER DOCUMENTS <i>(Including Author, Title, Date, Pertinent Pages, Etc.)</i>								
JRC		Kodama et al., "Synthesis of Novel Fluoropolymer for 157nm Photoresists by Cyclo-polymerization", Proc. SPIE, Vol. 5690, Part 1, pp. 76 - pp. 83 (2002)						
JRC		Copy of International Search Report (Form PCT/ISA/210) for PCT/EP2004/001194						
EXAMINER 				DATE CONSIDERED 				
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.								